

Application No.: 10/824,266

Docket No.: JCLA12868

**AMENDMENTS****In The Claims**

Claim 1 (currently amended) A varactor, comprising:

a ~~second~~ first type substrate;

two gate structures, disposed over the ~~second~~ first type substrate, each of the gate structures comprising an inter-gate dielectric layer and a gate conductive layer on the inter-gate dielectric layer;

a first second type doped region, disposed in the ~~second~~ first type substrate between the two gate structures; and

a ~~second~~ first type doped region, disposed in the ~~second~~ first type substrate at a side of the two gate structures apart from the first second type doped region;

wherein the first second type doped region is electrically connected to a first electrode, and the ~~second~~ first type doped region is electrically connected to a second electrode, and the two gate structures are electrically connected with the first electrode or the second electrode.

Claim 2 (currently amended) The varactor of claim 1, wherein the ~~first~~ second type doped region is a p-type doped region, and the ~~second~~ first type doped region is an n-type doped region.

Claim 3 (currently amended) The varactor of claim 1, wherein the ~~first~~ second type doped region is an n-type doped region, and the ~~second~~ first type doped region is a p-type doped region.

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Claim 4 (original) The varactor of claim 1, further comprising:

a polycide layer, disposed over the gate conductive layer, the first type doped region and the second type doped region.

Claim 5 (currently amended) The varactor of claim 1, further comprising:

a ~~first~~ second type lightly doped region, disposed in the ~~second~~ first type substrate adjacent to the ~~first~~ second type doped region; and

a ~~second~~ first type lightly doped region, disposed in the ~~second~~ first type substrate adjacent to the ~~second~~ first type doped region.

Claim 6 (original) The varactor of claim 5, further comprising:

a spacer, disposed over a sidewall of each of the gate structures covering the first type lightly doped region and the second type lightly doped region.

Claim 7 (currently amended) A differential varactor, comprising:

at least one pair of varactors, disposed over a ~~second~~ first type substrate, wherein each of the varactors comprising:

a first varactor, the first varactor comprising:

two first gate structures, disposed over the ~~second~~ first type substrate and each of the first gate structures comprising a first inter-gate dielectric layer and a first gate conductive layer on the first inter-gate dielectric layer;

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a ~~first~~ second type first doped region, disposed in the ~~second~~ first type substrate between the two first gate structures; and

a ~~second~~ first type first doped region, disposed in the ~~second~~ first type substrate at a side of the two first gate structures apart from the ~~first~~ second type first doped region; and

a second varactor, adjacent to the first varactor, the second varactor comprising:

two second gate structures, disposed over the ~~second~~ first type substrate, and each of the second gate structures comprises a second inter-gate dielectric layer and a second gate conductive layer on the second inter-gate dielectric layer;

a ~~first~~ second type second doped region, disposed in the ~~second~~ first type substrate between the two second gate structures; and

a ~~second~~ first type second doped region, disposed in the ~~second~~ first type substrate at a side of the two second gate structures apart from the ~~first~~ second type second doped region, wherein the ~~second~~ first type second doped region is adjacent to the ~~second~~ first type first doped region,

wherein, the first gate structure and the ~~first~~ second type first doped region are electrically connected to a tuning voltage, and the second gate structure and the ~~first~~ second type second doped region are electrically connected to a relative tuning voltage, and the ~~second~~ first type first doped region and the ~~second~~ first type second doped region are grounded.

Claim 8 (currently amended) The differential varactor of claim 7, wherein the first type ~~first~~ second doped region and the ~~first~~ second type second doped region are p-type doped regions,

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and the ~~second~~ first type first doped region and the ~~second~~ first type second doped region are n-type doped regions.

Claim 9 (currently amended) The differential varactor of claim 7, wherein the first type ~~first~~ second doped region and the ~~first~~ second type second doped region are n-type doped regions, and the ~~second~~ first type first doped region and the ~~second~~ first type second doped region are p-type doped regions.

Claim 10 (currently amended) The differential varactor of claim 7, further comprising:  
a polycide layer, disposed over the first gate conductive layer, the second gate conductive layer, the first type first doped region, the first type second doped region, the second type first doped region and the second type second doped region.

Claim 11 (currently amended) The differential varactor of claim 7, further comprising:  
a ~~first~~ second type lightly doped region, disposed in the ~~second~~ first type substrate adjacent to the ~~first~~ second type first doped region; and  
a ~~second~~ first type lightly doped region, disposed in the ~~second~~ first type substrate adjacent to the ~~second~~ first type first doped region .

Claim 12 (original) The differential varactor of claim 11, further comprising:  
a spacer, disposed over a sidewall of each of the first gate structures covering the first type lightly doped region and the second type lightly doped region.

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Claim 13 (currently amended) The differential varactor of claim 7, further comprising:

a ~~first~~ second type lightly doped region, disposed in the ~~second~~ first type substrate adjacent to the ~~first~~ second type second doped region ; and

a ~~second~~ first type lightly doped region, disposed in the ~~second~~ first type substrate adjacent to the ~~second~~ first type second doped region.

Claim 14 (original) The differential varactor of claim 13, further comprising:

a spacer, disposed over a sidewall of each of the second gate structures covering the first type lightly doped region and the second type lightly doped region.